Large area SEM mapping using the Rapid Stage and its benefits for EDS, WDS and micro-XRF analysis



Bruker Nano Analytics, Berlin, Germany Webinar, April 30th, 2020

XRF Mass Comb. Mass Val. /M% [%] Norm. EDS Mass [%] Norm. 46.82 [%] Norm. Line S. 10.68 45.58 10.61 45.71 **K**-Series 10.54 0.95 **K-Series** 0.89 33.70 0.89 **K-Series** 34.18 1.34 34.99 **K**-Series 0.34 33.94 0.35 series

0.16



Quantax micro-XRF

Rapid Stage

Quantax EDS

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Ba Au Ni

MAG: 37X HV: 50KV

Presenters





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- Terminology
- Introduction to Rapid Stage
- Types of Large Area Mapping on a SEM and Potential Issues
- Differences between SEM-EDS / SEM-WDS / SEM-XRF -Rapid Stage Technical Description
- Example Applications and Benefits
- Summary and Conclusion

Introduction Terminology

SEM-EDS: Analysis based on the sample interaction with an electron beam source from the SEM and the resultant X-rays that are detected using an EDS (simultaneous element detection)

SEM-WDS: Analysis based on the sample interaction with an electron beam source from the SEM and the resultant X-rays that are detected using a WDS (sequential element detection)

SEM-XRF-EDS: MicroXRF on SEM (XTrace): Analysis based on the sample interaction with an X-ray beam source from the Micro XRF attached to the SEM and the resultant X-rays that are detected using an EDS (simultaneous element detection)

Rapid Stage: New high speed stage with precision movement

SEM Stage: Standard stage that comes with the SEM









Analytical Parameters and Conditions SEM-EDS vs SEM-WDS vs SEM-XRF



Parameter	EDS: E-beam (SEM-EDS)	WDS: E-beam (SEM-WDS)	EDS: Micro-XRF (SEM-XRF-EDS)	
Analyzed Volume	Ø: few µm Information depth: µm; (depending primarily on electron energy)	Ø: few µm Information depth: µm; (depending primarily on electron energy)	Ø: 15-30 μm Information depth: μm to mm; (depending on analysed element and matrix)	
Detectable Elements	Atomic number Z ≥ 4 (beryllium)	Atomic number $Z \ge 4$ (beryllium)	Atomic number $Z \ge 6$ (carbon)	
Energy range	K- L –M – Lines (up to 20 keV)	70 eV – 3.6 keV (L- M- Lines)	K- L –M – Lines (up to 40 keV)	
Concentration Range	Down to 1000 ppm	Down to 100 ppm	Down to 10 ppm	
Quantification	Standard less and Standard based	Standard based	Standard less and standard based	
Data collection	Simultaneously	Sequentially	Simultaneously	
Sample Preparation	Sample needs to be electrically conductive (commonly carbon- coated), polishing required	Sample needs to be electrically conductive (commonly carbon- coated), polishing required	Electrical Conductivity not required, samples doesn´t need to be polished	
Sample Stress	Heating due to absorbed electrons	Heating due to absorbed electrons	Minimal	
Typical SEM beam current	Variable	Variable > 10 nA	N/A	

Introduction Historic and Current Webinars



www.bruker.com/events/webinars.html

Filter: EDS, WDS, EBSD, Micro-XRF on SEM

High Speed Mapping Using Micro-XRF on SEM



Advanced elemental analysis of geological samples using QUANTAX WDS for SEM



Bruker Nano Analytics, Berlin, Germany Webinar, April 25, 2019



Application of Rapid Stage Motivation



Why using Rapid Stage for SEM-EDS and SEM-WDS?

- Enhancing speed for mapping applications
- Enhancing EDS / WDS usability
- Enabling WDS mapping with vertical beam at the speed of a beammap
- Avoiding Bragg's law violation
- Avoiding lateral intensity loss
- Enabling large scale mapping

Why using Rapid Stage for SEM-XRF?

 Enhancing speed for mapping applications as only stage mapping is possible as the X-ray beam is fixed in space and can not be rastered

Rapid Stage for SEM's Introduction









- The Rapid Stage has been developed to enable high-speed mapping over large areas via Stage movement
- It is mounted on top of an existing SEM stage, including stage adaption and sample holder.
- The Rapid Stage is controlled independently from the SEM stage and can operate up to a maximum travel speed of 4 mm/s.





5/1/2020

32 mm

Rapid Stage Dimensions

Stage itself (including x- and y linear positioners and basis plate): **27 mm** Including footplate: **32 mm**

Without dovetail and sample holder \rightarrow SEM depending



27 mm



for Hitachi S3700N setup: 73 mm



Rapid Stage Integration in ESPRIT





5/1/2020

Introduction Video Rapid Stage



Rapid Stage Installations: Adaptable to various SEMs



Jeol IT-500



Hitachi S 3700N





Jeol JSM 6490



Hitachi SU 3900

Rapid Stage Specification



Parameter	Description			
Height	27 mm (without sample holder and SEM stage adaption)			
Weight	300 g			
Sample load	3 kg			
Stage travel speed	4 mm /sec			
Travel distance	50 mm			
Vacuum resistance	10 ⁻⁶ mbar (higher vacuum resistance on request)			
Resolution	< 1 nm			

Examples





Rapid Stage Examples - Settings



Large Area Maps Overview: Mapping Types

Source: Electron Beam (e-beam) and X-ray beam

Detector: EDS and WDS

Stage: SEM-Stage and Rapid Stage

Note: Combination (Simultaneous) data-sets

Rapid Stage with e-beam + X-ray beam + EDS, or

Rapid Stage with e-beam + EDS and WDS

Large Area Mapping 3 Different Mapping Modes





Increasing accuracy - WDS

Increasing speed – SEM Stage

Sample 1 Sulphide bearing rock

magnification 45x Image dimensions: 2.9 x 2.2 mm

Low

Resolution: 2000 x 1500 px $(1.45 \,\mu m / px)$





Sample 2 Garnet-Spinel Peridotite





Low magnification 45x

Image dimensions: 2.9 x 2.2 mm

Resolution: 1200 x 900 px (2.4 µm / px)

Sample 3 Electronics Microchip





Low magnification 30x

Image dimensions: 4.3 x 3.2 mm

Resolution: 1200 x 900 px (3.6 µm / px)

Large Area Mapping Type I





Scan Map Without Range Limits Sample 1 at low magnification Single Field





Type I Mapping: Low Magnification – Single Field Problems for WDS Mapping due to violation of Bragg's Law Scan Map Without Range Limits Sample 2 at low magnification Single Field





Type I Mapping: Low Magnification – Single Field Problems for WDS Mapping due to violation of Bragg's Law Scan Map Without Range Limits Sample 3 at low magnification Single Field





Type I Mapping: Low Magnification – Single Field Problems for WDS Mapping due to violation of Bragg's Law

Scan Map Without Range Limits Sample 3 at low magnification **Single Field**







El Tesoro Deposit

01.05.2020

Scan Map Without Range Limits Sample 1 at high magnification Single Field





Type I Mapping: High Magnification – Single Field Suitable method for Small Areas where Bragg Angle Effect is negligible Scan Map Without Range Limits Sample 3 at high magnification Single Field





Type I Mapping: High Magnification – Single Field Suitable method for Small Areas where Bragg Angle Effect is negligible

Large Area Mapping Type II





Scan Mapping with Range Limits Sample 1 at low magnification Segmented Map: 29 x 22 Tiles





✓ Faster than stage map ✓ Intensity fading reduced

- Slower than scan map without limits
- Tiling may be visible

Type II Mapping: Low Magnification – Multiple Tiles 29 x 22

Bragg Angle Effect is lowered but may still be visible in mosaics

69

44

Scan Mapping with Range Limits Sample 2 with Tiling at low magnification Extended Map: 29 x 22 Tiles



Type II Mapping: Low Magnification – Multiple Tiles 29 x 22 Bragg Angle Effect is lowered but may still be visible in mosaics

Large Area Mapping Type IIIa: SEM Stage





Stage Mapping using SEM Stage Sample 1 at low magnification SEM-EDS/WDS







 $120 \times 90 = 10,800 \text{ px} \rightarrow 10 \text{ h}$ $1200 \times 900 = 1,080,000 \text{ px} \rightarrow 42.5 \text{ d}$ Type IIIa Mapping: Low Magnification – Single Field Equivalent High Analytical Time due to slow SEM Stage Movement

For SEM-EDS/WDS:

Not Practical or Realistic use of Analytical Equipment.

For SEM-XRF (Micro-XRF) This is standard method, but slow. Fixed X-ray beam. Stage Mapping using SEM Stage Sample 2 at low magnification SEM-EDS/WDS



Effective time: 3.4 s / per pixel



Type IIIa Mapping: Low Magnification – Single Field Equivalent High Analytical Time due to slow SEM Stage Movement

Stage Mapping using SEM Stage Sample 2 at low magnification SEM-XRF



Large Area Map Sample Size: Polished Section: 45 x 30 mm

Sample from El Tesoro, Chile.

Clearly Defined Elemental and Mineralogical Phases Can identify the presence of trace elements, in this case, Cobalt (Co), Manganese (Mn), Strontium (Sr)

Analytical Parameters:

Tube Voltage: Rh at 50 kV Anode Current: 600 µA Pixel Spacing: 25 µm

 Analytical Time:
 Rapid Stage 101 mins
SEM Stage >800 mins



Top: Elemental Maps; Bottom Left: Mixed Elemental Map; Bottom, Right: X-Ray Intensity Map.



Large Area Mapping Type IIIb: Rapid Stage





Stage Mapping using Rapid Stage Sample 1 at low magnification

Stage Mapping using Rapid Stage Sample 1 at low magnification

2.9 mm Со Ti 2.2 mm Dwell time: 4 ms / px WX Co, LA1 WX Ti, KA1 Analytical time: 1 h / Ca frame

Stage Mapping using Rapid Stage Sample 1 at low magnification

Stage Mapping using Rapid Stage Sample 2 at low magnification

Stage Mapping using Rapid Stage Sample 3 at low magnification

Stage Mapping using Rapid Stage Sample 3 at low magnification

Stage Mapping using Rapid Stage Sample 3 extended area: 4x4

Stage Mapping using Rapid Stage Sample 3 extended area

Stage Mapping using Rapid Stage Sample 3 extended area

Stage Mapping using Rapid Stage Sample 2 extended area: 3x3

Stage map using Rapid Stage Sample 2 extended area

Stage Mapping using Rapid Stage Sample 2 extended area

Stage Mapping using Rapid Stage Sample 2 extended area

Stage Mapping using Rapid Stage Effect of acquisition time

Increasing Information

Increasing Analytical Speed

Stage Mapping using Rapid Stage Effect of beam current

Large Area Mapping Summary Mapping Types I, II, IIIa and IIIb

	FOV (mm)	FOV (px)	WDS Dwell time (ms/px)	Time /image (min)	Remarks
Type I: Raster Map	2.9 x 2.2	1200 x 900	8	60	Lateral intensity loss
Type II: Raster Map with Tiles	2.9 x 2.2	1200 x 900	8	360	Tiling may be visible
Type IIIa: SEM Stage Map	2.9 x 2.2	1200 x 900	8	60,480	Extremely slow
Type IIIb: Rapid Stage Map	2.9 x 2.2	1200 x 900	8	144	Fast and correct

Comparing mapping types Sample 1 at low magnification

- Extremely fast Inaccurate
- at low magnificat ion

- ✓ Relatively fast
- Tiling may be visible

Accurate
 Extremely slow

✓ Very fast✓ Accurate

Summary and Conclusions: Rapid Stage Benefits

Fast mapping

- Increase in speed by significant factor:
 - Especially for WDS and SEM-XRF use
- Enhancing WDS and SEM-XRF usability
- SEM Stage communication not designed for on-the-fly measurment

Accurate results

- Mapping with a vertical beam
- Avoiding violation of Bragg conditions
- Avoiding lateral intensity loss
- Supports simultaneous analysis with e-beam and X-ray beam or EDS and WDS.

Summary and Conclusions: Rapid Stage and Micro-XRF

- Can work in combination with SEM e-beam
 - Commonly Low-KV due to charging and sample interaction
- > The analysis of samples in mircometers (μ m) scale on a standard SEM.
- Able to perform large area maps on a variety of samples.
- Sample Preparation Minimal for Micro-XRF
 - No carbon-coating
 - No polishing
 - Directly into the SEM
- > Able to detect and resolve minor and trace elements
- Identification of high energy X-Ray lines

Questions and Answers

Are There Any Questions?

Please type in the questions you might have in the Q&A box and press *Send*. More Information

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